Additions and Corrections

A. M. Wróbel, A. Walkiewicz-Pietrzykowska, Y. Hatanaka, S. Wickramanayaka, and Y. Nakanishi: Oligomerization and Polymerization Steps in Remote Plasma Chemical Vapor Deposition of Silicon-Carbon and Silica Films from Organosilicon Sources.

This paragraph, indicating the availability of Supporting Information, was inadvertently omitted from this article (*Chem. Mater.* **2001**, *13*, 1884−1895):

Tables of mass spectrometric data of the conversion products of hexamethydisilane, trimethylsilane, and tetraethoxysilane recorded at the ionizing electron energy of 70 eV (PDF). This material is available free of charge via the Internet at http://pubs.acs.org.

CM012004O

10.1021/cm012004o
Published on Web 07/27/2001

2001, Volume 13

Dong Wook Kim,* Alexandre Blumstein,* and Sukant K. Tripathy: Nanocomposite Films Derived from Exfoliated Functional Aluminosilicate through Electrostatic Layer-by-Layer Assembly.

Because of an oversight omitting the name of one of the contributors, Dr. Jayant Kumar, the title page data for this article (*Chem. Mater.* **2001**, *13*, 1916−1922) should read as follows:

Nanocomposite Films Derived from Exfoliated Functional Aluminosilicate through Electrostatic Layer-by-Layer Assembly

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CM0120069

10.1021/cm0120069
Published on Web 07/10/2001